

**INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION**

ATTY. DOCKET NO.
49959-220

SERIAL NO.

APPLICANT
Gilad ALMOGY, et al.

FILING DATE
November 07, 2001

GROUP

(PTO-1449)

J1050 U.S. PTO
09/986137
11/07/01

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
<i>EF</i>	5,248,876	9/28/1993	Kerstens et al.			
<i>EF</i>	5,900,637	5/4/1999	Smith			
<i>EF</i>	6,248,988	9/19/2001	Krantz			

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
<i>EF</i>	EP0871052A1	10/14/1998	Europe				

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>EF</i>	"Projection X-Ray Lithography Using Arrays of Zone Plates", M. Feldman, Electrical & Computer Engineering Department, pp. 136-144.
<i>EF</i>	"Zone-plate-array lithography in the deep ultraviolet", Ihsan J. Djomehri et al., American Vacuum Society, 1998, pp. 3426-3429.
<i>EF</i>	"Zone-Plate Array Lithography (ZPAL): A new maskless approach", D.J.D. Carter et al., Part of the SPIE Conference on Emerging Lithographic Technologies III, March 1999. pp. 324-332.
<i>EF</i>	"Use of Zone Plate Arrays in Projection X-Ray Lithography", M. Feldman, Electrical and Computer Engineering Department, Louisiana State University, 1993, pp. 207-207.
<i>EF</i>	"A proposal for maskless, zone-plate-array nanolithography", Henry I. Smith, American Vacuum Society, 1996, pp. 4318-4322.
<i>EF</i>	"Maskless, parallel patterning with zone-plate array lithography", D.J.D. Carter et al., American Vacuum Society, 1999, pp. 3449-3452.
<i>EF</i>	"Confocal principle for macro- and microscopic surface and defect analysis", Hans J. Tiziani et al., Society of Photo-Optical Instrumentation Engineers, 2000, pp. 32-39.
<i>EF</i>	"Lithographic patterning and confocal imaging with zone plates", Dario Gil et al., American Vacuum Society, 2000, pp. 2881-2885.
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5-28-03

SHEET 1 OF 1

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EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		US 6,248,988 B1	08/19/01	Krantz	
		US 6,043,932	03/28/00	Kusunose	
		US 6,133,986	10/17/00	Johnson	
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		US 5,248,876	09/28/93	Kerstens et al.	
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		US 6,208,413 B1	03/27/01	Vaez-Iravani	
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EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Code ¹ -Number -Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No
		WO 98/57151	12/17/98	PCT			
		0678864 A1	11/02/95	Europe			
		0647828 A2	04/12/95	Europe			
		0298432 A2	01/18/89	Europe			
		01263541	10/2089	Japan		X Abstract	
		2000066374	03/03/00	Japan		X Abstract	

OTHER ART (including Author, Title, Date, Patent, Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		Partial International Search Report dated 5/5/03.

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¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

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		US 6,040,909	03/21/00	Hasegawa et al.	
		US 6,248,988	06/19/01	Krantz	
		US 6,130,428	10/10/00	Pasch	
		US 5,932,966	08/03/99	Schneider et al.	
		US 3,894,332	07/15/75	Nathanson et al.	
		US 2003/0042434 A1	03/06/03	Mankos et al.	
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						Yes	No
		GB 2339860 A	02/09/00	United Kingdom			
		WO 01/84585 A1	11/08/01	PCT			
		WO 02/23172 A2	03/21/02	PCT			
		EP 0948027 A2	10/06/99	Europe			
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EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		International Search Report dated August 4, 2003.
		"High throughput electron lithography with the multiple aperture pixel by pixel enhancement of resolution concept", Krull, P., J. Vac. Sci. Technol. B 16(6), Nov/Dec 1998.
		"Microlens arrays with spatial variation of the optical functions", Hessler, Th., et al., Pure Appl. Opt. 6(1997) 673-681.
		"A Microlens Direct-Write Concept for Lithography", Davidson, M., SPIE 3048, p. 346-355.
		"Immersion lithography at 157 nm", Swikes, M. et al., J. Vac. Sci. Technol. B, Vol. 19, No. 6, Nov/Dec 2001, pp. 2353-2356.
		"Liquid immersion deep-ultraviolet interferometric lithography", Hoffnagle, J. et al., Vac. Sci. Technol. B 17(6), Nov/Dec 1999, pp. 3306-3309.
		"An Overview of the Performance Envelope of Digital Micromirror Device (DMD) Based Projection Display Systems", Sampell, J. B., Society for Information Display 1994 International Symposium (San Jose, Jun. 12-17, 1994), pp. 1-4.
		"UV Thermoresist: Sub 100nm Imaging Without Proximity Effects", Gelbart, D. et al., SPIE Vol. 3676, pp. 786-793.

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